Synchrotron Radiation to study Atomic Layer Deposition

Tuesday, 14 June 2016

Talks 4 (14:30 - 18:15)

time	[id] title	presenter
14:30	[38] Live monitoring of ALD by ambient pressure x-ray photoelectron spectroscopy	Prof. SCHNADT, Joachim
15:15	[39] The MOON reactor: optimizing oxyde nanostructures ALD by combining in situ synchrotron X-ray and optical analysis	Prof. RENEVIER, Hubert
16:00	[25] Aluminum Nitride Grown by Atomic Layer Epitaxy Characterized with Real-Time Grazing Incidence Small Angle X-ray Scattering	Dr ANDERSON, Virginia
16:20	[22] Near-Ambient Pressure X-ray Photoelectron Spectroscopy Study of the Atomic Layer Deposition of HfO2 on SiO2 / Si	Dr YEROMONAHOS, Christelle
16:40	Coffee break	
17:00	[27] Thin, low roughness Ru films deposited by thermal and plasma enhanced atomic layer deposition using RuO□ and H□ at low temperatures	Mr MINJAUW, Matthias
17:20	[4] An atomistic view of the incipient growth of zinc oxide by in-situ x-ray absorption spectroscopy	Dr CIATTO, Gianluca
17:40	[16] In Situ Synchrotron-based XRF and GISAXS Study of ALD Encapsulation of Supported Nanocrystals	Dr DENDOOVEN, Jolien
18:00	[40] Open Session proposals	